

## N THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	<ul> <li>) Confirmation No. 4499</li> <li>)</li> <li>) Group Art Unit: 1765</li> <li>)</li> <li>) Examiner: ALANKO A. K.</li> </ul>
Inventor(s): Li Yao et al.	
Appln. No.: 10/689,043	
Filed: October 21, 2003	
For: ABRASIVE-FREE CHEMICAL MECHANICAL POLISHING COMPOSITION AND POLISHING PROCESS CONTAINING SAME	) )

## RESPONSE UNDER 37 C.F.R. §1.111

U.S. Patent and Trademark Office Randolph Building 401 Dulany Street Alexandria, Virginia 22314 MAIL STOP – AMENDMENT

Sir:

In response to the Office Action mailed on August 9, 2006 please consider the following amendments and remarks:

Amendments to the claims begin on page 2 of this paper.

Remarks begin on page 6 of this paper.